



Nanoimprint Lithography: Principles, Processes & Materials

By Hongbo Lan, Yucheng Ding, Hongzhong Liu

Nova Science Publishers Inc. Paperback. Book Condition: new. BRAND NEW, Nanoimprint Lithography: Principles, Processes & Materials, Hongbo Lan, Yucheng Ding, Hongzhong Liu, Lithography, the fundamental fabrication process of semiconductor devices, has been playing a critical role in micro-nanofabrication technologies and manufacturing of Integrated Circuits (IC). Traditional optical lithography including contact and project photolithography has contributed significantly to the semiconductor device advancements. Currently, maintaining the rapid pace of half-pitch reduction requires overcoming the challenge of improving and extending the incumbent optical projection lithography technology while simultaneously developing alternative, next generation lithography (NGL) technologies to be used when optical projection lithography is no longer more economical than the alternatives. Furthermore, NIL is also one of the most promising low-cost, high-throughput technologies for manufacturing nanostructures as this highly technical book will give new insight to.



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